# IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Minna Hovinen et al.

Application No.: NEW

Filed: HEREWITH

For: METHOD FOR DETERMINING ION CONCENTRATION AND ENERGY OF

SHALLOW JUNCTION IMPLANTS

Group Art Unit: Unknown

Examiner: Unknown

INFORMATION DISCLOSURE STATEMENT

121 Spear Street, Suite 290 San Francisco, CA 94105

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M/S PATENT APPLICATION Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

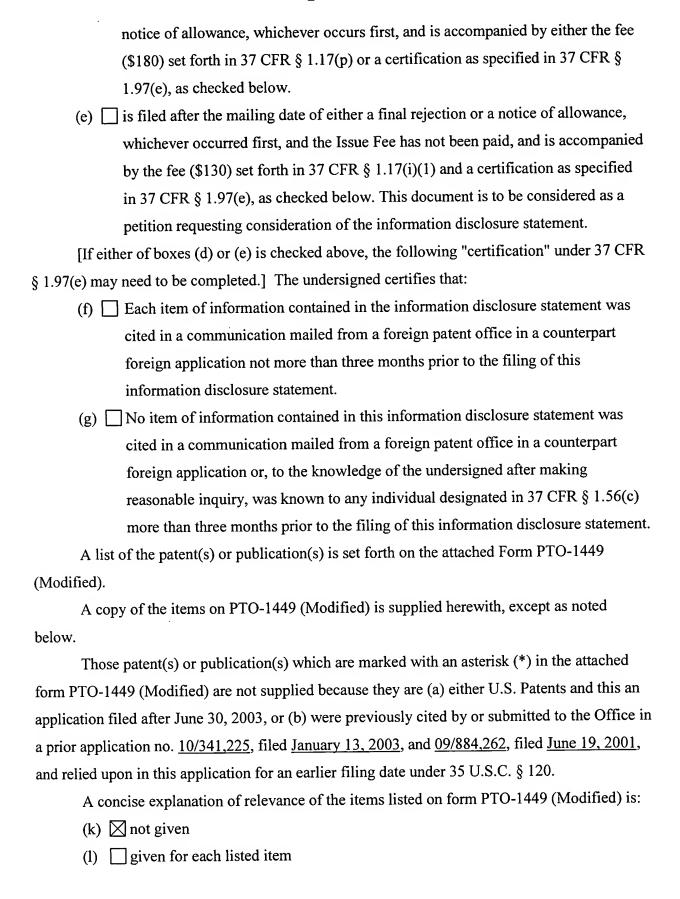
Sir:

Applicant(s) submit(s) herewith patents, publications or other information [attached hereto and listed on the attached Form PTO-1449 (modified)] of which they are aware, which they believe(s) may be material to the examination of this application and in respect of which there may be a duty to disclose in accordance with 37 CFR § 1.56.

This Information Disclosure Statement:

- (a) accompanies the new patent application submitted herewith. 37 CFR § 1.97(a).
  (b) is filed within three months after the filing date of the application or within three months after the date of entry of the national stage of a PCT application as set forth in 37 CFR § 1.491.
  (c) as far as is known to the undersigned, is filed before the mailing date of a first
- (c) as far as is known to the undersigned, is filed before the mailing date of a first Office Action on the merits, or before a first office action after filing a Request for Continued Examination under §1.114.
- (d) is filed after the first office action and more than three months after the application's filing date or PCT national stage date of entry filing but, as far as is known to the undersigned, prior to the mailing date of either a final rejection or a

Atty Docket No.: TWI-12730



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- (m) given for only non-English language listed item(s) [Required]
- (n) is in the form of an English language copy of a Search Report from a foreign patent office, issued in a counterpart application, which refers to the relevant portions of the references [copy attached].

The Examiner is reminded that a "concise explanation of the relevance" of the submitted items "may be nothing more than identification of the particular figure or paragraph of the patent or publication which has some relation to the claimed invention," MPEP § 609.

While the information and references disclosed in this Information Disclosure Statement may be "material" pursuant to 37 CFR § 1.56, it is not intended to constitute an admission that any patent, publication or other information referred to therein is "prior art" for this invention unless specifically designated as such.

In accordance with 37 CFR § 1.97(g), the filing of this Information Disclosure Statement shall not be construed to mean that a search has been made or that no other material information as defined in 37 CFR § 1.56(a) exists. It is submitted that the Information Disclosure Statement is in compliance with 37 CFR § 1.98 and MPEP § 609 and the Examiner is respectfully requested to consider the listed references.

Respectfully submitted,

STALLMAN & POLLOCK LLP

Dated: October 1 , 2003

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Atty Docket No.: TWI-12730

# INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

Docket Number (Optional)	Application Number
TWI-12730	NEW
Applicant(s)	
Minna Hovienen et al.	
Filing Date	Group Art Unit
HEREWITH	Unknown

### **U.S. PATENT DOCUMENTS**

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	*AA	4,522,510	06/11/1985	Rosencwaig et al.	374	7	04/01/1983
	*AB	4,636,088	01/13/1987	Rosencwaig et al.	374	5	05/21/1984
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	*AE	4,999,014	03/12/1991	Gold et al.	356	382	05/04/1989
	*AF	5,074,669	12/24/1991	Opsal	356	445	12/12/1989
	*AG	5,181,080	01/19/1993	Fanton et al.	356	381	12/23/1991
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### FOREIGN PATENT DOCUMENTS

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REF	NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	YES	No
 *AP	WO 99/02970	01/21/1999	PCT	G01N	21/21		
 *AO	WO 00/68656	11/16/2000	PCT	G01J	4/00		

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(Including Author, Title, Date, Pertinent Pages, Etc.)

 *AR	L. Zhou et al., "Use of a New Thermal Wave Technology for Ultra-Shallow Junction Implant Monitoring," Proceedings of
	the X International Conference on Ion Implantation Technology, June 1998, Kyoto (Japan), pp. 1-4.
*AS	A. Salnick et al., "Quantitative Photothermal Characterization of Ion-Implanted Layers in Si," 25th Review of Progress in
1	ONDE, Snowbird (Utah), July 19-24, 1998, pp. 1-15.
 *AT	U.S. Patent Application No. 09/499,974, filed February 8, 2000, entitled "Combination Thermal Wave and Optical
	Spectroscopy Measurement System,". (5 drawing pages included) by Jon Opsal et al., 29 pages in length.

Examiner	Date Considered			
Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if				
not in conformance and not considered. Include copy of this form with next communication to applicant.				